

# EUROPEAN PATENT OFFICE

## Patent Abstracts of Japan

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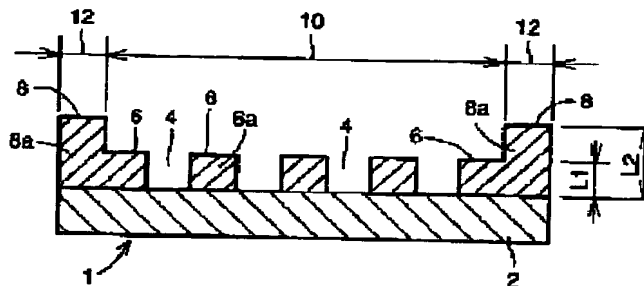
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APPLICANT : MITSUBISHI ELECTRIC CORP;

INVENTOR : MIYAZAKI JUNJI;

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TITLE : ATTENUATING TYPE PHASE SHIFT MASK AND METHOD AND DEVICE FOR MANUFACTURING IT



ABSTRACT : PURPOSE: To provide an attenuating type phase shift mask which has a pattern that prevents the generation of exposure beams around the correct exposure area and prevents exposure to the adjacent exposure area when continuous exposure is performed by shifting.

CONSTITUTION: An attenuating type phase shift pattern area 10 is provided with the attenuating type phase shift pattern area 10 and an auxiliary pattern area 12 that surrounds the attenuating type phase shift pattern area 10. The attenuating type phase shift pattern area 10 is provided with a first light transmitting part 4 which exposes a transparent glass board 2 and a second light transmitting part 6 which has a phase angle of 180° and a transmission factor of 40% or less. The auxiliary pattern area 12 is provided with a third light transmitting part 8 which has a smaller transmission factor than the second light transmitting part 6.

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